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#1
(((tmah, tetramethylammonium hydroxide, tetramethyl amonium hydroxide<in>metadata) <and> (glycol, propylene glycol<in>metadata))<and> (etch*, clean*, remov*<in>metadata)) <and> (pyr >= 1950 <and> pyr <= 2004)

#2
(((tmah, tetramethylammonium hydroxide, tetramethyl amonium hydroxide<in>metadata) <and> (glycol, propylene glycol<in>metadata))<and> (etch*, clean*, remov*<in>metadata)) <and> (pyr >= 1950 <and> pyr <= 2004)

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EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L37	256	(HAZ or (heat$6 adj affect$6) or (damag$6 near5 (laser or heat$6 or thermal or anneal$6))) and (TMAH or (tetramethylammonium adj hydroxide) or (tetramethyl adj ammonium adj hydroxide) or tetramethylammoniumhydroxide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/04 21:39
L38	220	37 and (@ad<"20040319" or @rlad<"20040319")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/04 21:40
L39	96	38 and (HAZ or (heat$6 adj affect$6) or (damag$6 near5 (laser or heat$6 or thermal or anneal$6))or TMAH or (tetramethylammonium adj hydroxide) or (tetramethyl adj ammonium adj hydroxide) or tetramethylammoniumhydroxide) same (Si or silicon or polySi or polysilicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/04 21:41

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L29	15797	(TMAH or (tetramethylammonium adj hydroxide) or (tetramethyl adj ammonium adj hydroxide) or tetramethylammoniumhydroxide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/04 21:31
L30	11516	29 and (glycol or propyleneglycol or glycerol or alcohol or OH or OH?sup$3 or (organic near10 solvent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/04 21:34
L31	2402	30 and ((Si or silicon or polysilicon or polySi) near15 (etch$6 or clean$6 or remov$6))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/04 21:34
L32	2008	31 and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/04 21:34
L33	1862	32 and (@ad<"20040319" or @rlad<"20040319")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/04 21:34
L34	3054	29 same (glycol or propyleneglycol or glycerol or alcohol or OH or OH?sup$3 or (organic near10 solvent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/04 21:34
L35	642	33 and 34	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/04 21:34